

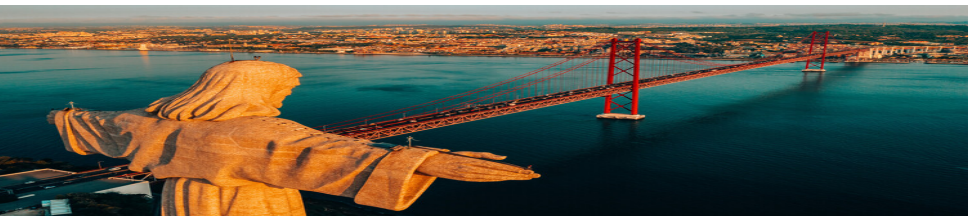
Timing Characterization of 1 cm² LGAD pads for Space Experiments

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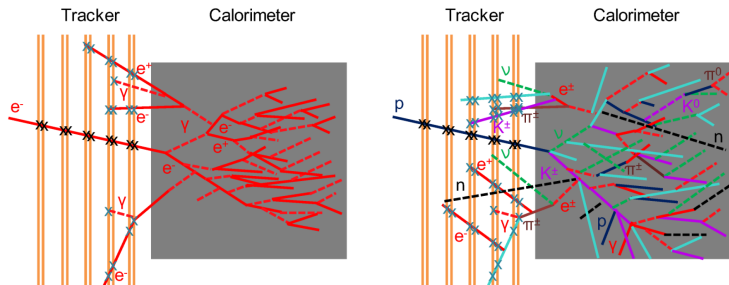


July 2, 2024

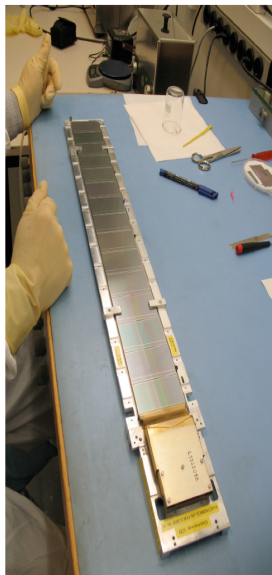
25th International Workshop On Radiation Imaging Detectors(iWoRiD)



Time resolving tracking in space experiments



- ▶ **Timing $\sim 50\text{-}100$ ps**
- ▶ Identification of back-scattered hits from calorimeters
- ▶ Time-of-flight (ToF) measurement
→ typically done using scintillators
- ▶ Improved e/p identification



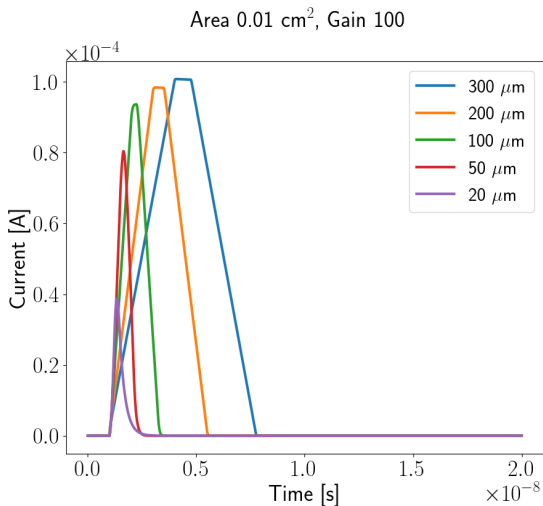
- ▶ Large area to cover $\rightarrow \mathcal{O}(m^2)$
- ▶ Power constraint
 \rightarrow Reduce $N_{channels}$
- ▶ Small particle flux \rightarrow Large channel size
- ▶ “Typical” Silicon sensor for space
 \rightarrow Strips (100 μm pitch)
 \rightarrow 60-100 cm long
 $\rightarrow \sim 1 \text{ cm}^2$
- ▶ LGAD: suitable for timing
- ▶ LGAD channel size for HEP $\sim 1\text{-}2 \text{ mm}^2$
 $\rightarrow \sigma_t \approx 30 \text{ ps}$ for Min. Ioniz. Particle (MIP)

Scaling LGAD channel size to 1 cm^2

Capacitance?

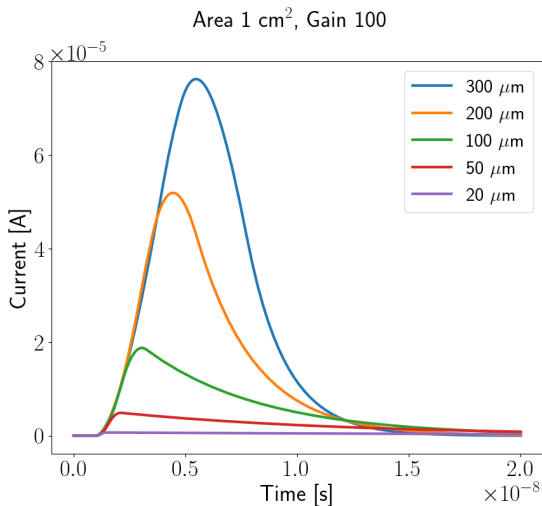
Time resolution?

- ▶ LTspice simulation
- ▶ Sensor capacitance
- ▶ Uniform charge deposition (No Landau fluctuations)
- ▶ Saturated velocities
- ▶ Noise = Amplifier \oplus Sensor



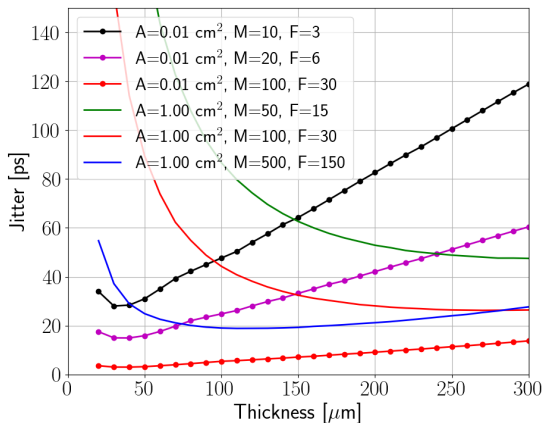
[M. Centis Vignali et al. VCI (2022)]

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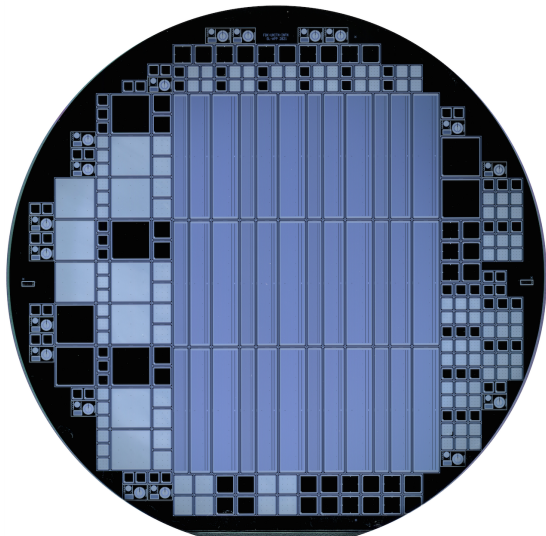


LGAD thickness $> 100 \mu\text{m}$, gain ≈ 100

[M. Centis Vignali et al. VCI (2022)]

Production of large LGAD sensors under the INFN project

- ▶ A total of 16 wafers
- ▶ Pad and strip sensors
- ▶ Strips: 100 μm , 150 μm , 200 μm pitch
- ▶ Active thickness:
→ 50, 100, and 150 μm
- ▶ Gain implant dose and energy optimized for high gain using TCAD
- ▶ Optimized for large areas
- ▶ Signal propagation

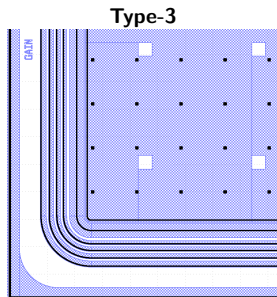
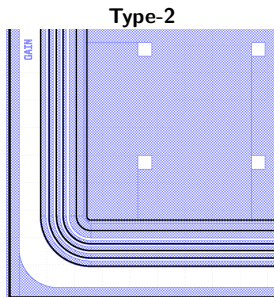
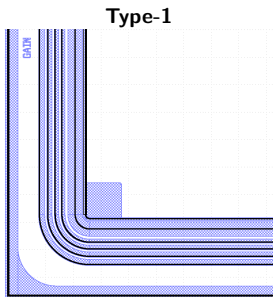


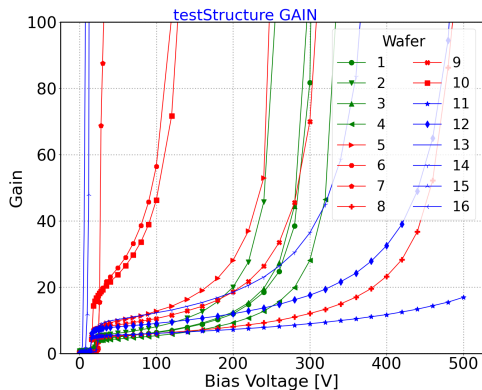
▶ Pad active area:

- A (6.25 mm^2)
- B (25 mm^2)
- C (100 mm^2)

▶ Pad types:

- **Type-1:** Metal frame
- **Type-2:** Fully Metallized, Contacts at the edge of the active area
- **Type-3:** Fully Metallized, Contacts covers all active area

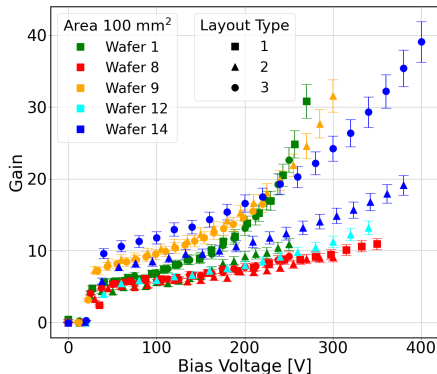




- ▶ Operating temperature = 24° with illumination.

$$Gain|_{LED} = \frac{(I_{light} - I_{dark})|_{LGAD}}{(I_{light} - I_{dark})|_{PIN}}$$

- ▶ value of gain highly depends on the dose and energy of the implant
- ▶ Early breakdown:
 - 100 μm → 6, 7, 10
 - 150 μm → 13, 15, 16
- ▶ 50 μm: gain of $\mathcal{O}(10)$, $200 \leq V_{bd} \leq 300$
- ▶ 100 μm wafer 8, 9
- ▶ 150 μm wafer 11, 12, and 14



- ▶ Laser intensity: 1 MIP

$$Gain = \frac{Q_{LGAD}}{Q_{PIN}}$$

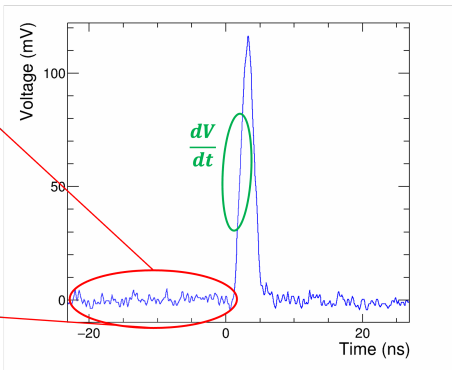
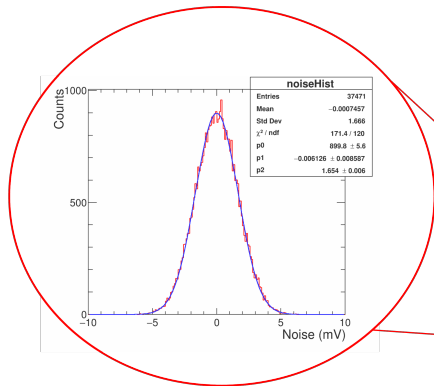
- ▶ The gain trend is consistent with the gain measured from the test structures using LED.
- ▶ The impact ionization model used for this work tend to overestimate the gain.

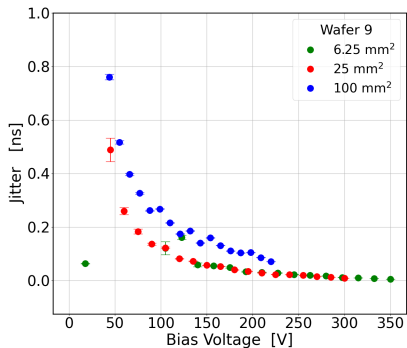
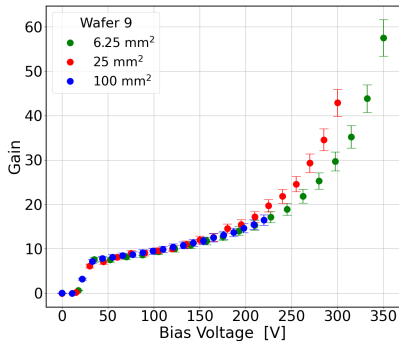
- ▶ Errors account for uncertainties due to amplifier response evaluated through repeated measurements
- ▶ The non-uniformity of gain among the devices from same wafer is due to the non-uniformity in the implant dose of the gain layer.

Jitter Measurements

$$\sigma_{jitter} = \frac{\sigma_{Noise}}{Slew\ Rate\ (dV/dt)}$$

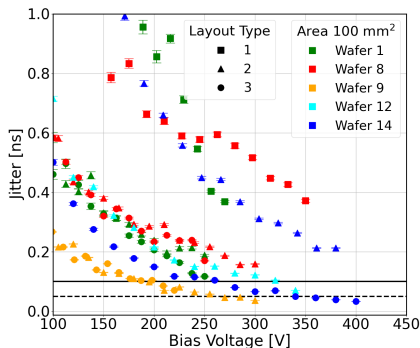
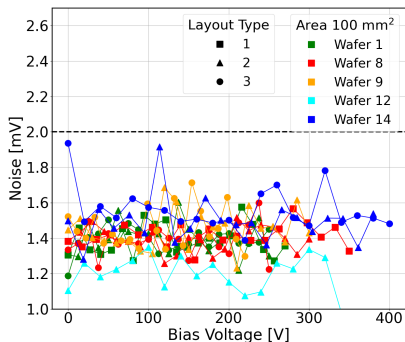
- ▶ Measurement (no averaging in Oscilloscope) → Noise estimation
- ▶ Measurement (256 averages in Oscilloscope) → Slew rate estimation
- ▶ Slew-Rate: slope of the line that best fits the leading edge between 20% and 80% of signal amplitude



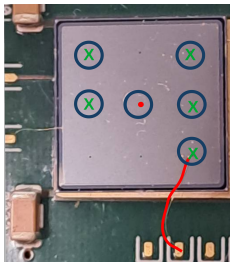


- ▶ 100 μm thick sensors
- ▶ Smaller active areas result in a steeper leading edge with higher amplitude
- ▶ Collected charge is practically the same

Jitter Measurements: 1 cm² sensors



- ▶ The average noise remains below 2 mV
- ▶ Lack of trend → shot noise is not the dominant noise figure in the system
- ▶ $\sigma_{jitter} < 100$ ps : wafer 9, 12, and 14
- ▶ $\sigma_{jitter} < 50$ ps : 36 ps for wafer 9 (100 μ m), and 34 ps for 14 (150 μ m)

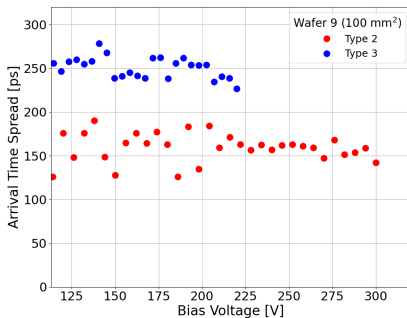


- ▶ Reference point is the signal near to the bond
- ▶ **Hit position**
- ▶ **X** = Check points for uniformity
- ▶ Contribution of the arrival time to the timing resolution is:

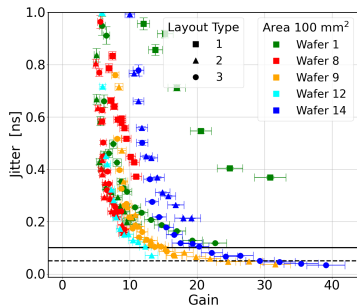
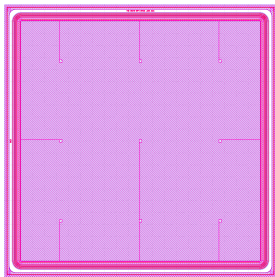
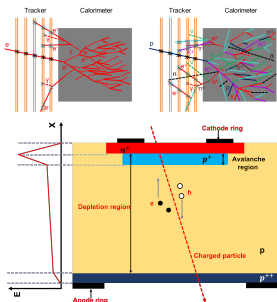
$$\sigma_{uni} = \frac{153}{\sqrt{12}} \text{ ps} \approx 44 \text{ ps}$$

- ▶ Time resolution due to jitter and non-uniformity of the signal shape at 300 V is:

$$\sigma_t = \sigma_{Jitter} \oplus \sigma_{uni} \approx 60 \text{ ps}$$

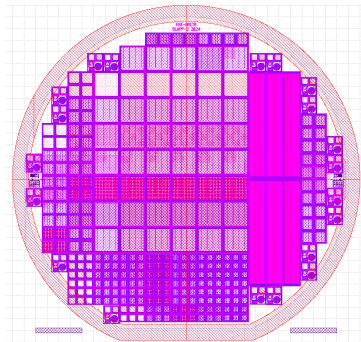


- ▶ Include timing measurement for each hit/track in the silicon tracker
- ▶ LGADs → suitable candidate based on the timing performance for HEP experiments
- ▶ Increase the active area of the LGADs
→ Gain $\sim \mathcal{O}(100)$ and Thickness ($>100 \mu\text{m}$)
- ▶ Space LGADs production optimized to study large area LGADs
- ▶ Jitter under 40 ps for 1 cm² LGADs, and $\sigma_t \approx 60$ ps including non-uniformity effects



Future prospects

- ▶ New production batch to further study the timing resolution and effects of signal propagation
- ▶ Time resolution using particle source



**THANK YOU
FOR YOUR
ATTENTION**